

1) "MOSFET" \rightarrow Metal Oxide Semiconductor Field Effect Transistor

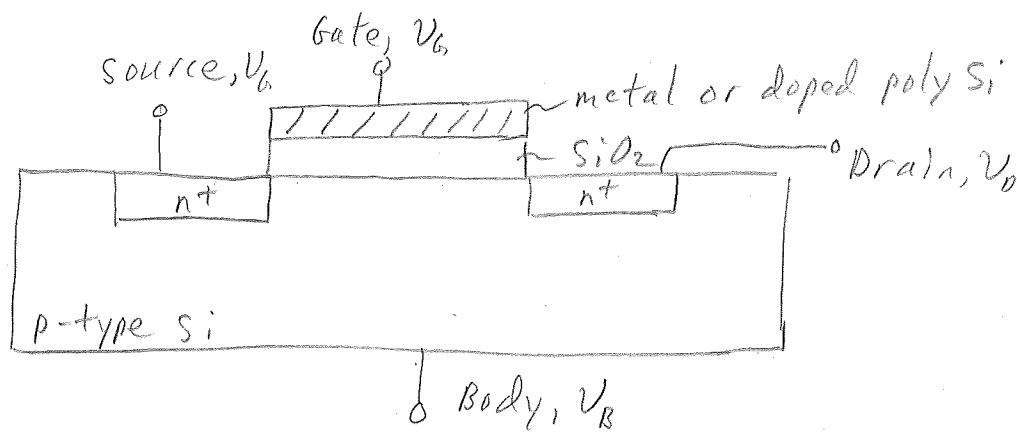
n-type and p-type MOSFETs

n-type: n-type source and drain in p-type substrate

p-type: p-type " " " " n-type "

a. Discussion on n-type MOSFET

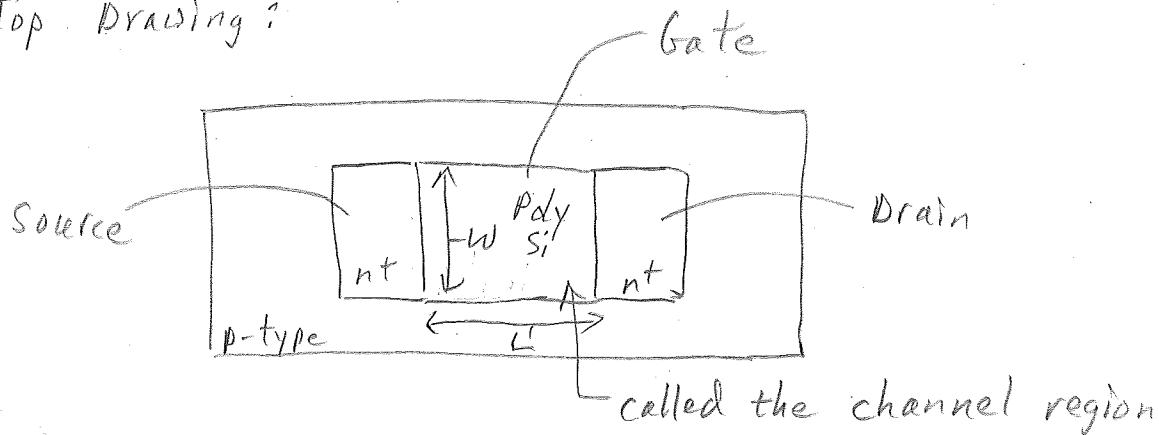
Cross-sectional Drawing:



note: metal contacts on source and drain not shown

$$V_B \leq V_S \text{ and } V_D \geq V_S$$

Top Drawing:



The channel region is defined by W and L . The designer defines W and L to tailor the MOSFET's characteristics.

$\frac{W}{L}$ is an important MOSFET parameter

In this MOSFET device, applying V_{GS} enhances the conductivity of the channel $\Rightarrow \therefore$ these are called Enhancement-Mode MOSFETs

Later, we will discuss Depletion-Mode MOSFETs

Since the MOSFET is based on the MOS capacitor, i_G and i_B are OA \rightarrow DC currents

Note : AC currents will flow through a capacitor

$$Z(j\omega) = \frac{1}{j\omega C} \text{ for a capacitor}$$

\therefore the current of interest is the current from Drain to Source, referred to as i_D

3 primary modes of operation

① Off

when $V_{GS} - V_{TN} < 0V \therefore i_D = 0A$

② Linear or Triode Region of operation

$$V_{GS} - V_{TN} \geq 0 \text{ and } V_{GS} - V_{TN} \geq V_{DS}$$

$$i_D = K_n' \frac{W}{L} \left(V_{GS} - V_{TN} - \frac{V_{DS}}{2} \right) V_{DS}$$

$$K_n' = \mu_n C_{OX}'' = \mu_n \frac{\epsilon_{ox}}{T_{ox}} = \frac{\epsilon_0 \epsilon_r}{T_{ox}}$$

for Si, $\epsilon_r = 3.9$

$$\epsilon_0 = 8.854 \text{ pF/m}$$

μ_n = electron mobility

C_{OX}'' = oxide capacitance per unit area, in F/cm^2

$$K_n = K'_n \frac{W}{L}$$

K_n and K'_n → called transconductance parameters

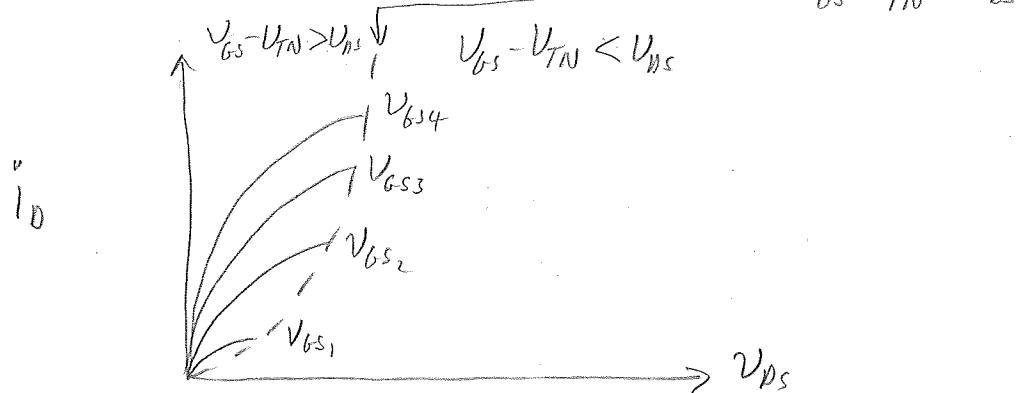
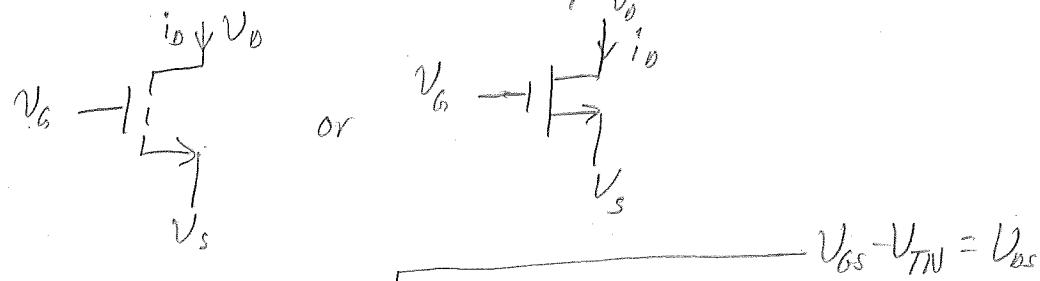
$$[K_n] = [K'_n] = A/V^2$$

$$\text{For } i_D = K_n (V_{GS} - V_{TN} - \frac{V_{DS}}{2}) V_{DS} = K'_n \frac{W}{L} (V_{GS} - V_{TN} - \frac{V_{DS}}{2}) V_{DS}$$

→ The Designer gets to define $\frac{W}{L}$ in the design

Since V_B is often shorted to V_s → effectively 3 terminals in the NMOS Transistor: V_G, V_S, V_D

Different schematic symbols:



Plot of i_D vs. V_{DS} for different values of V_{GS}

where $V_{GS4} > V_{GS3} > V_{GS2} > V_{GS1}$

$$\text{ex: } V_{GS1} = 2V, V_{GS2} = 3V, V_{GS3} = 4V, V_{GS4} = 5V$$

$$\text{and } V_{TN} = 1V$$

Typical value for $K_n = 25 \times 10^{-6} A/V^2$

③ Saturation or Pinch-off Region

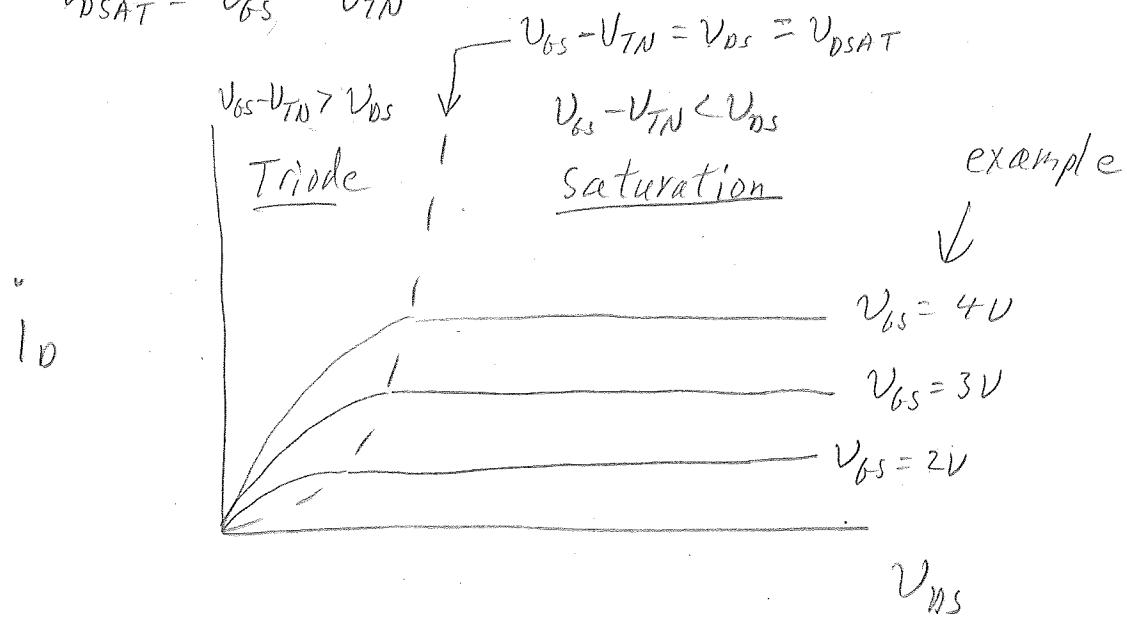
$$V_{GS} - V_{TN} \geq 0 \text{ and } V_{DS} \geq V_{GS} - V_{TN}$$

→ by further increasing V_{DS} beyond the Triode Region, it "no longer" increases i_D

$$\rightarrow i_D = \frac{k_n'(\mu)}{2} (W) (V_{DS} - V_{TN})^2 \rightarrow \text{square law response}$$

The channel is said to be "pinched-off"

$$V_{DSAT} = V_{GS} - V_{TN}$$



Triode Region: $i_D = f(V_{DS} \text{ and } V_{GS})$
 Saturation: $i_D = f(V_{GS})$

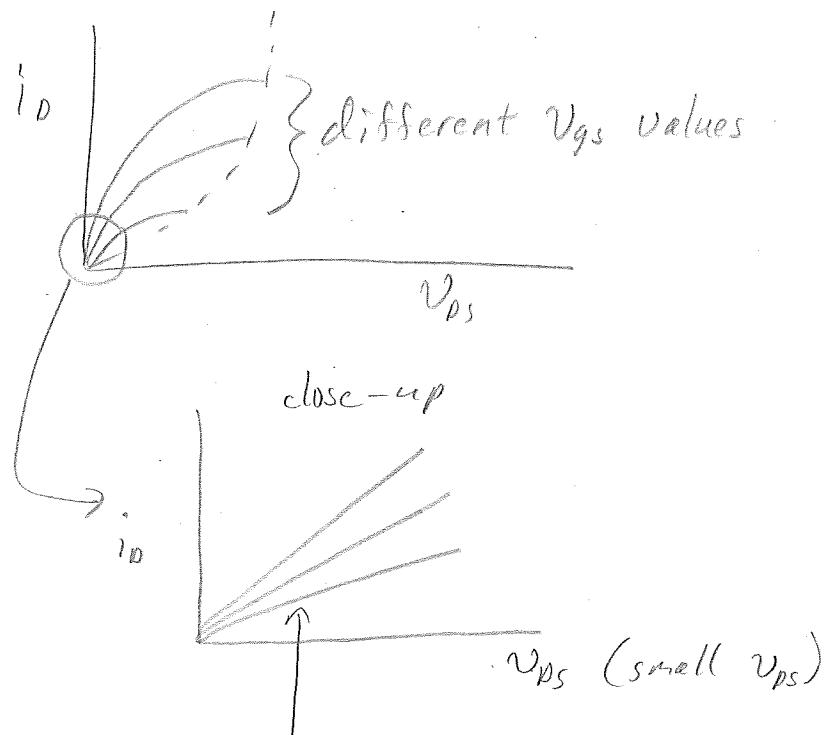
1st order model
for NMOS

Region usage

Triode → voltage controlled resistor, digital logic, analog switch
 Saturation → amplifier

2. More on Triode Region of operation

- "Triode" name → from similar operation to the triode vacuum tube
- Also called the "Linear Region"



nearly linear inc in i_D w/ V_{DS} inc

∴ For small V_{DS} ($\frac{V_{DS}}{2} \ll V_{GS} - V_{TN}$)

$$\rightarrow i_D \approx K_n' \left(\frac{w}{l} \right) (V_{GS} - V_{TN}) V_{DS}$$

$$\therefore \text{define } R_{on} = \left[\frac{\partial i_D}{\partial V_{DS}} \right]_{V_{DS} \rightarrow 0}^{-1} = \frac{1}{K_n' \left(\frac{w}{l} \right) (V_{GS} - V_{TN})}$$

notice that as $V_{GS} \uparrow$: $R_{on} \downarrow$

→ The nMOS transistor can be used as a voltage-controlled resistor, or as a resistive load by fixing V_{GS}

3. Transconductance : g_m

→ relates change in drain current to change in V_{GS} about the Q-point

→ useful in small-signal linear circuit model for MOSFET circuits

$$\text{def: } g_m = \left. \frac{\partial i_D}{\partial V_{GS}} \right|_{Q\text{-point}} \rightarrow \text{note error in book, eg 4.17 p. 153}$$

Triode Region

$$g_m = \left. \frac{\partial i_D}{\partial V_{GS}} \right|_{Q\text{-point}} = \left. \frac{\partial (K_n(V_{GS} - V_{TN}) - \frac{V_{DS}}{2})V_{DS}}{\partial V_{GS}} \right|_{Q\text{-point}} = K_n V_{DS}$$

DC value



Saturation Region

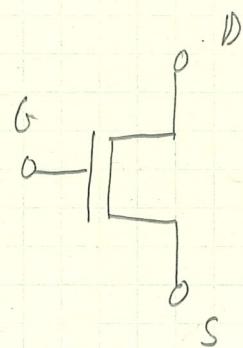
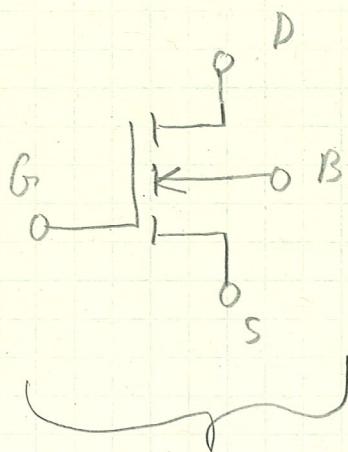
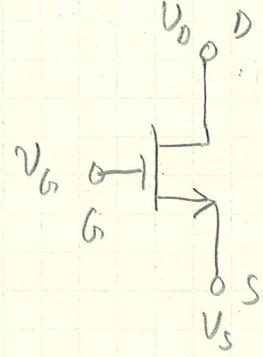
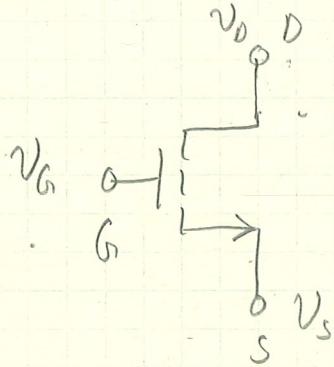
$$g_m = \left. \frac{\partial i_D}{\partial V_{GS}} \right|_{Q\text{-point}} = \left. \frac{\partial (\frac{1}{2}K_n(V_{GS} - V_{TN})^2)}{\partial V_{GS}} \right|_{Q\text{-point}} = K_n(V_{GS} - V_{TN})$$

DC value



Since V_{GS} is often a small signal input voltage and i_D is the small signal output signal, g_m represents a measure of the signal gain possible with the transistor circuit.

4) More schematic symbols for NMOS Transistors



Note : the circuit identifies S & D

here, the Body contact
may or may not be
tied to the source